

15.45/6059

**Version With Markings to Show Changes Made**

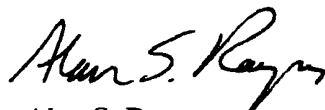
Claim 26 was amended as follows:

26. (amended)      A method as in claim 19, wherein the dielectric layer is formed using high density plasma chemical vapor deposition.

15.45/6059

It is believed that no fees are due relating to this submission, however, if fees are due relating to this submission, please charge them to deposit account no. 50-0585. A copy of this paper is enclosed.

Respectfully submitted,



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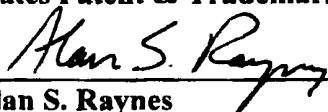
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Alan S. Raynes5/29/02  
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